

**Table S1.** Measured sheet resistances

Precursor	Thickness, nm	point1	point2	point3	point4	point5	$\Omega/\text{sq}$
TDMA-Ti	3	222.7	242.5	220.2	204.1222		
TDMA-Ti	3	207.8	185.9	171.8			
TDMA-Ti	3	177.9	206.4	201.9			
TDMA-Ti	6	171.5	281.5	238.6	230.5111		
TDMA-Ti	6	271.3	236.1	169			
TDMA-Ti	6	269	182.8	254.8			
TDMA-Ti	9	291.4	404.1	288.4	257.8444		
TDMA-Ti	9	300.8	193.4	275			
TDMA-Ti	9	194.1	195.4	178			
TDMA-Ti	12	174	176.2	173.7	174.9444		
TDMA-Ti	12	173.6	173.3	173.3			
TDMA-Ti	12	178.8	178.4	173.2			
TDMA-Ti	15	175	180	175.6	179.1667		
TDMA-Ti	15	179.6	178.2	181.2			
TDMA-Ti	15	180	182	180.9			
TDMA-Ti	20	171.4	181	174.5	201.3444		
TDMA-Ti	20	242.6	272.3	236			
TDMA-Ti	20		175.8	174.9	183.6		
TiCl <sub>4</sub>	3	569.5	555.5	535.4	546.7		
TiCl <sub>4</sub>	3	554	557.5	524.9	567.8		
TiCl <sub>4</sub>	6	375.5	6.557439	384	375	368	
TiCl <sub>4</sub>	6	390	18.28934	389	402	404	
TiCl <sub>4</sub>	6	378.5	30.68659	347	420	368	
TiCl <sub>4</sub>	9	345.6	349.3	285.1	455.2		
TiCl <sub>4</sub>	9	405.6	447.1	516	403.6		
TiCl <sub>4</sub>	9	661.8	1073	1032	1180		
TiCl <sub>4</sub>	12	976.45	151.7371	1019	967.8	1142	
TiCl <sub>4</sub>	12	519.75	143.9685	406	692	396	

$TiCl_4$	12	1008.2	266.6725	736	1384	768	
$TiCl_4$	15	1818	1395	1116	1197		
$TiCl_4$	15	1252.8	106.1965	1415	1248		
$TiCl_4$	15	1220	1261				
$TiCl_4$	20	3201	1476	4896	1817		
$TiCl_4$	20	1393	1483	1053	1488		

ce depending on the TiOx film thickness and used deposition precursor



**Figure S1.** Ellipsometry measurements of the deposited TiOx film at different temperatures for TDMA-Ti precursor (140 deposition cycles)